FIG. 1 (Prior Art)

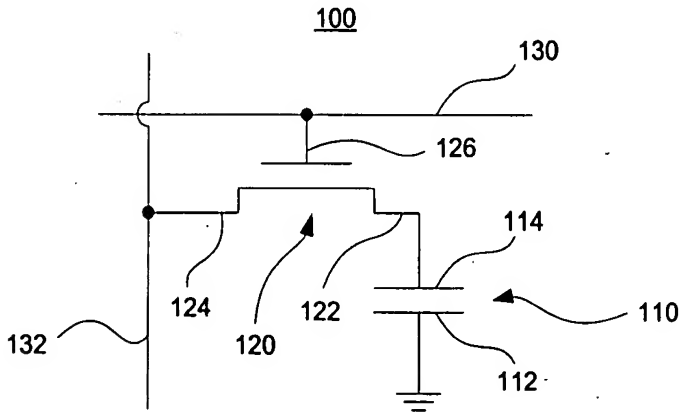


FIG 2

(Prior Art)

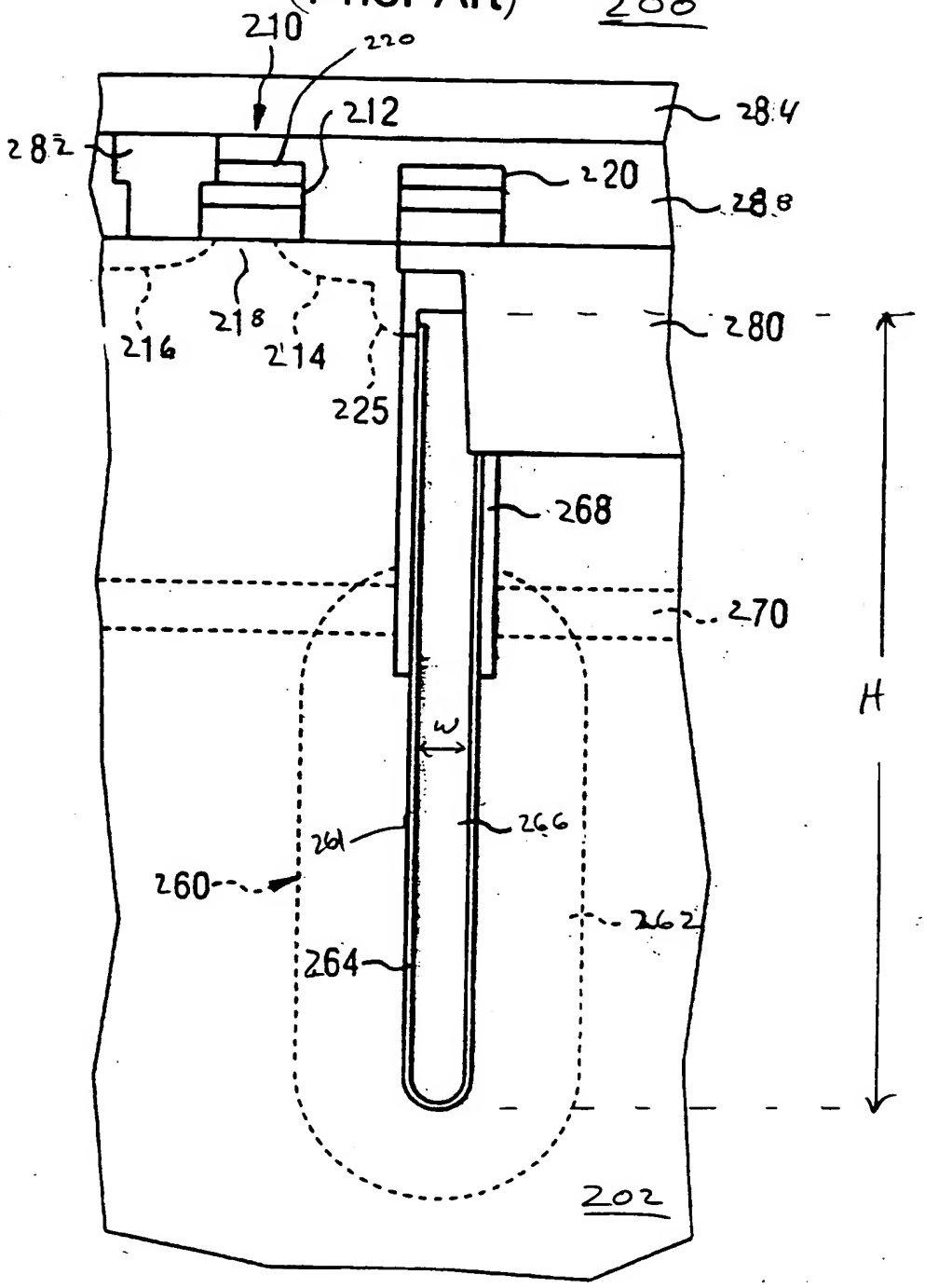


FIG. 3
(Prior Art)

300

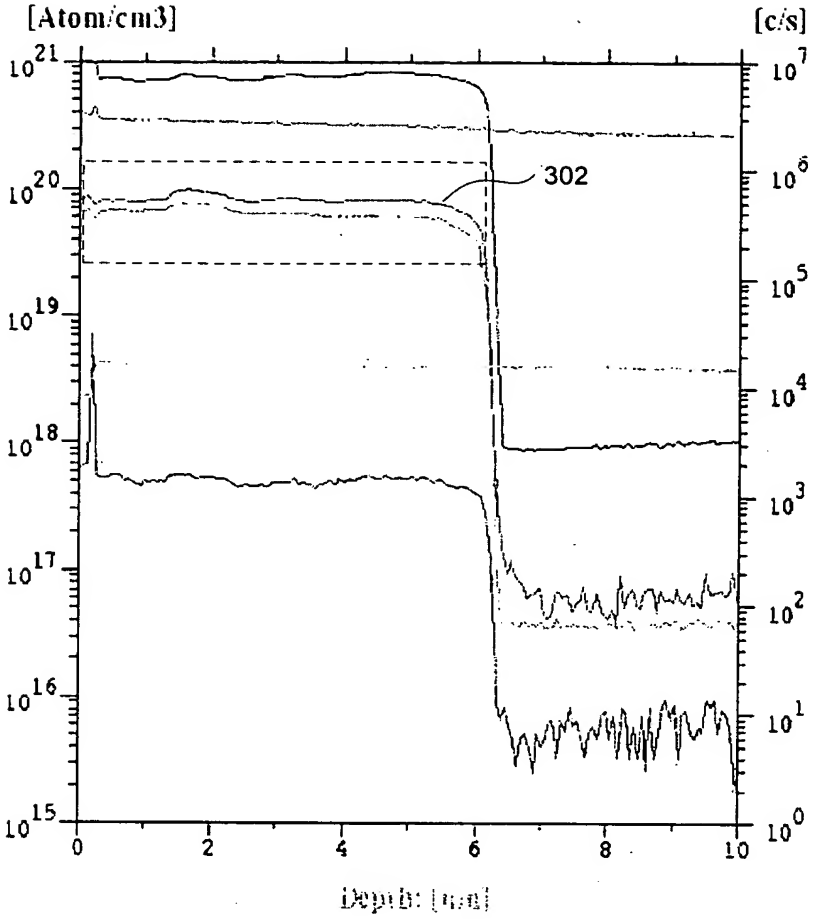


FIG. 4A

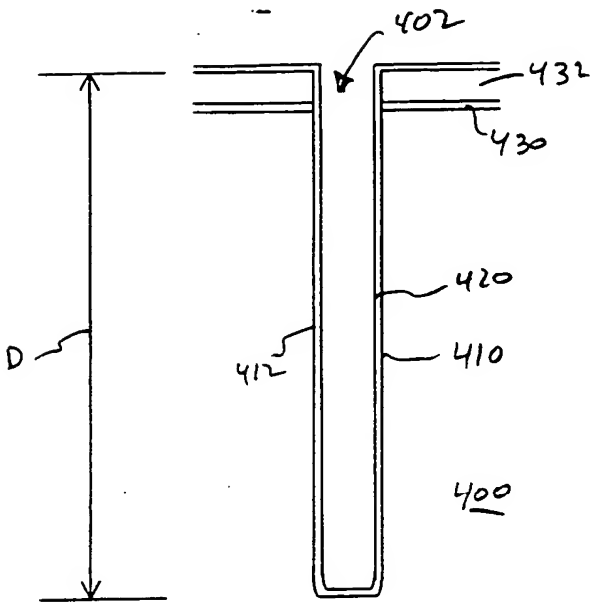
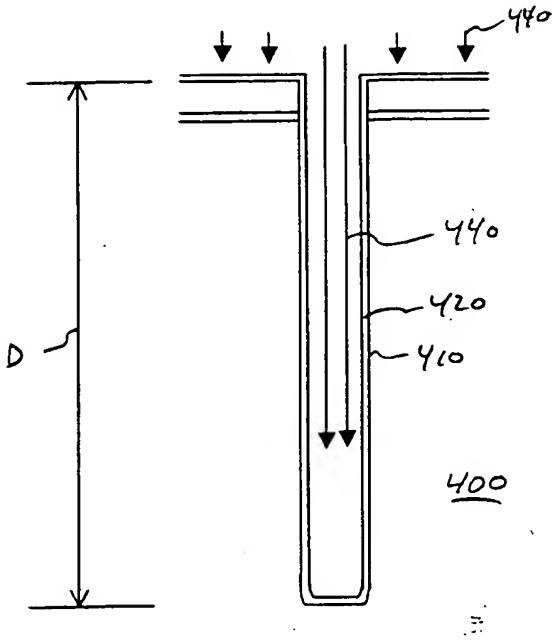


FIG. 4B



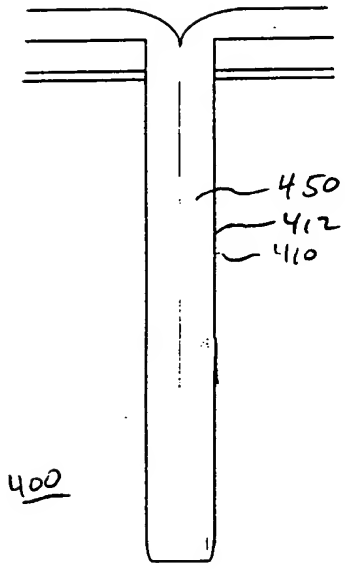
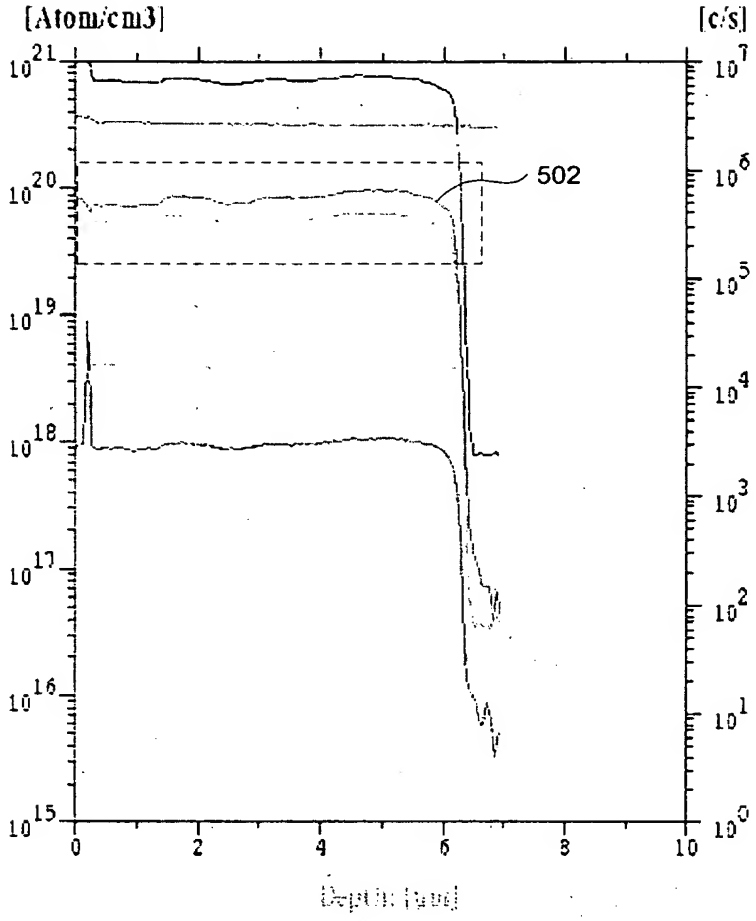


FIG. 4C

FIG. 5

500



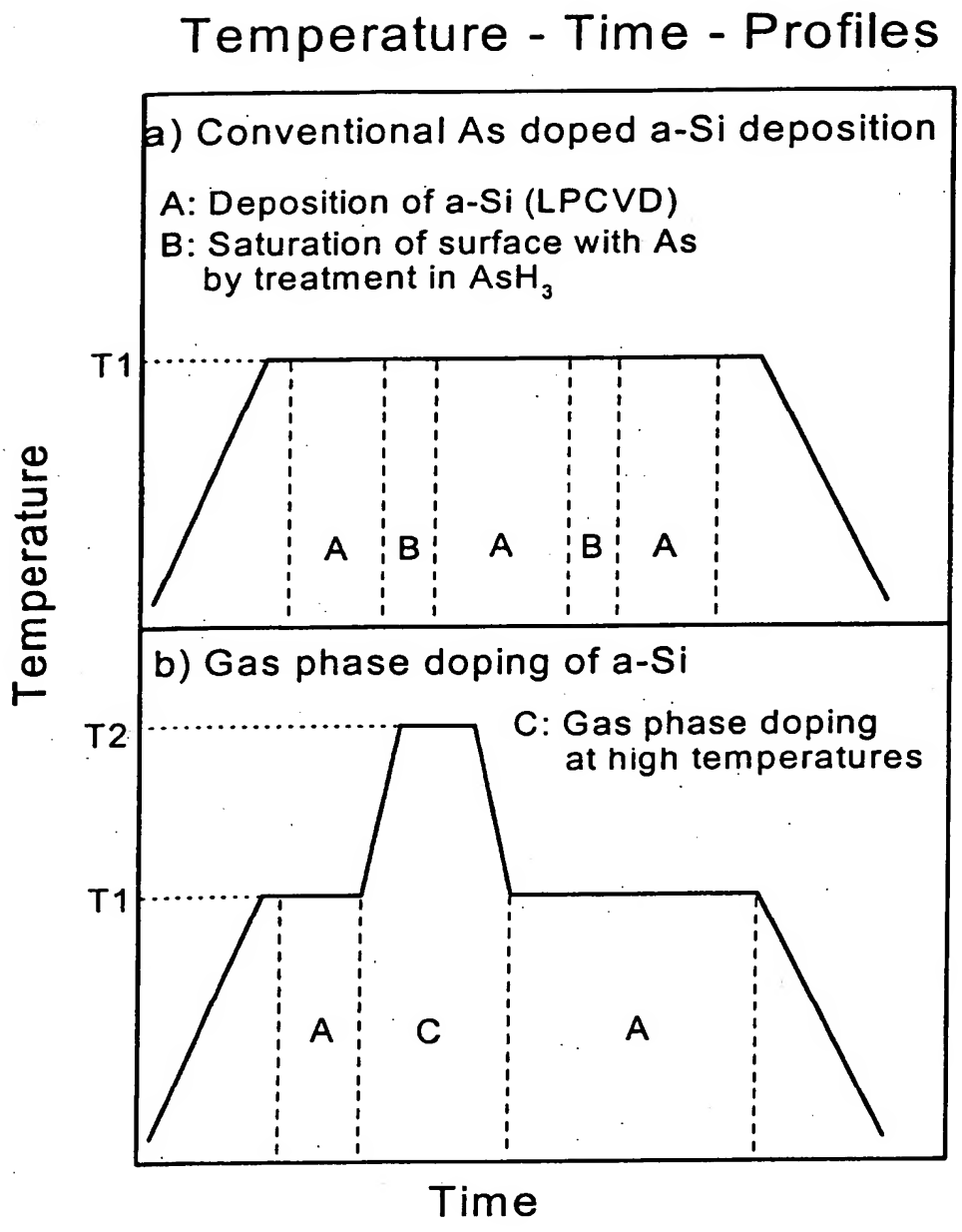

Temperature - Time - Profiles
a) Conventional As doped a-Si deposition
A: Deposition of a-Si (LPCVD)
B: Saturation of surface with As by treatment in AsH_3
T1
A
B
A
B
A
b) Gas phase doping of a-Si
C: Gas phase doping at high temperatures
T2
T1
A
C
A
Temperature
Time

FIG. 6A

FIG. 6B